Amendments to the Claims:

1. (previously amended) A CVD precursor solution including a solvent component and a hexacoordinated silicon beta-diketonate composition of the formula R_2Si(ß-diketonate)$_2$ or $(RO)_2Si$(ß -diketonate)$_2$, wherein each R is the same as or different from the other R, and each R is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl, .

2. (previously amended) The precursor solution of claim 1, wherein each ß -diketonate ligand of the composition may be the same as or different from the other ß -diketonate ligand of the composition, and is independently selected from: 2,2,6,6-tetramethyl-3,5-heptanedionate; 1,1,1,2,2,3,3-hepta-fluoro-7,7-dimethyloctane-4,6-dionate; acetylacetonate; trifluoro-acetylacetonate; and hexafluoroacetylacetonate.

3. (previously amended) The precursor solution of claim 1, wherein each ß -diketonate ligand of the composition is 2,2,6,6-tetramethyl-3,5-heptanedionate.

4. (previously amended) The precursor solution of claim 1, wherein the composition is of the formula R_2Si(ß -diketonate)$_2$.

5. (previously amended) The precursor solution of claim 1, wherein the composition is of the formula $(RO)_2Si$(ß -diketonate)$_2$.

6. (previously amended) The precursor solution of claim 1, wherein the composition is of the formula (t-BuO)$_2$Si(2,2,6,6-tetramethyl-3,5-heptanedionate)$_2$.

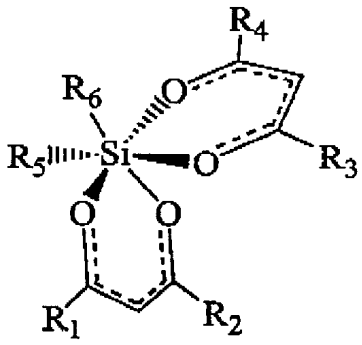
7. (previously amended) The precursor solution of claim 1, wherein the composition is of the formula (CH3)$_2$Si(2,2,6,6-tetramethyl-3,5-heptanedionate)$_2$.

8. (previously canceled)

9. (previously amended) The precursor solution of claim 1, wherein said solvent component comprises a hydrocarbon solvent.

10. (previously amended) The precursor solution of claim 1, wherein said solvent component comprises octane.

11. (previously amended) A precursor solution for use in chemical vapor deposition, comprising a solvent component and a silicon ß -diketonate of the formula:

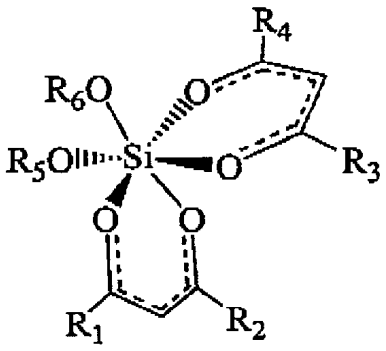


wherein:

R_1, R_2, R_3 and R_4 are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl; and

R_5 and R_6 are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.

12. (previously amended) A precursor solution for use in chemical vapor deposition, comprising a solvent component and a silicon ß -diketonate of the formula:



wherein:

R_1, R_2, R_3 and R_4 are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl and $C_1 - C_{12}$ silicon-containing alkyl; and

R_5 and R_6 are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.

13-38. (previously canceled)

39. (currently amended and previously added) A novel composition ~~comprising~~ **having the formula** $(t\text{-OBu})_2Si(thd)_2$.

40. (currently amended and previously added) A novel composition ~~comprising~~ **having the formula** $(CH_3)_2Si(thd)_2$.

41. (new) A CVD precursor solution including a solvent component and a hexacoordinated silicon beta-diketonate composition of the formula $R_2Si(\beta\text{-diketonate})_2$ or $(RO)_2Si(\beta\text{-diketonate})_2$, wherein each R is the same as or different from the other R, and each R is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl, wherein said solvent component comprises octane.